

Gamma Radiation Induced Effects in Si p-i-n Photo Diodes

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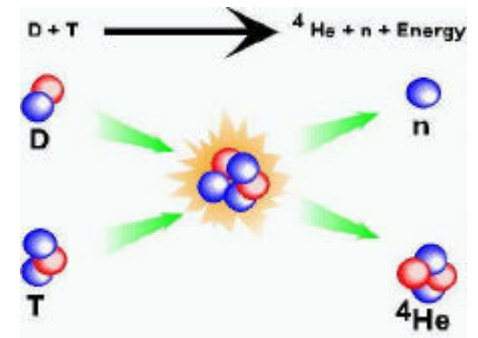
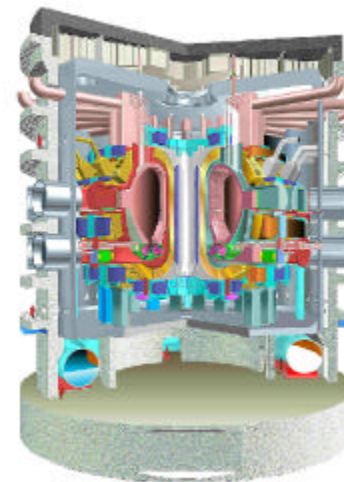
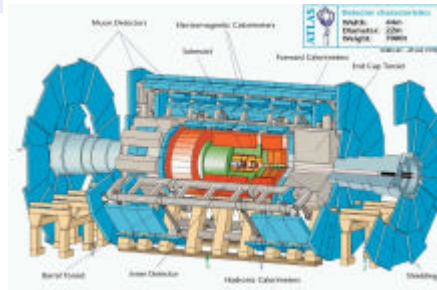
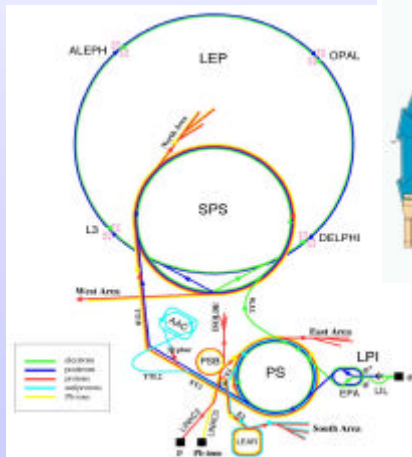
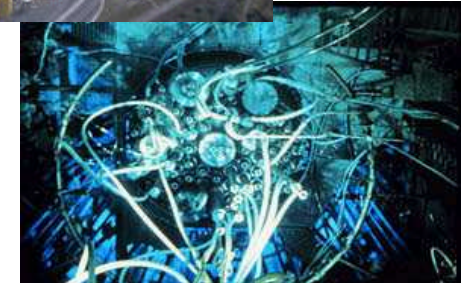
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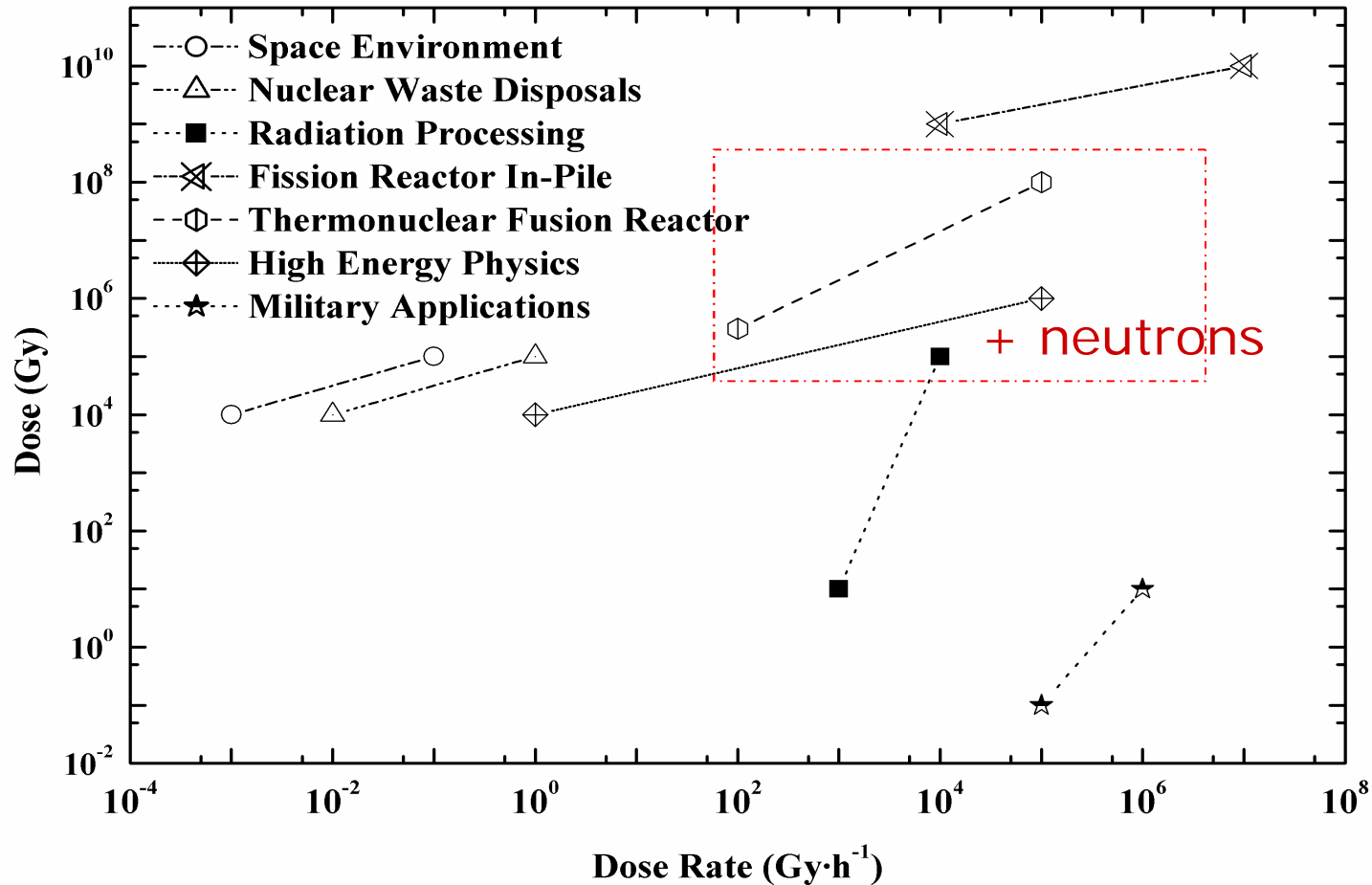
5-th RD-50 meeting, Florence, October 15th, 2004

- **Problem statement**
 - Objectives
 - Approach
- **Progress**
 - Physics
 - First calculations
- **Summary and Perspectives**

Instrumentation Department: studies of opto-electronics for applications in different nuclear environments



We mainly focus on high gamma doses



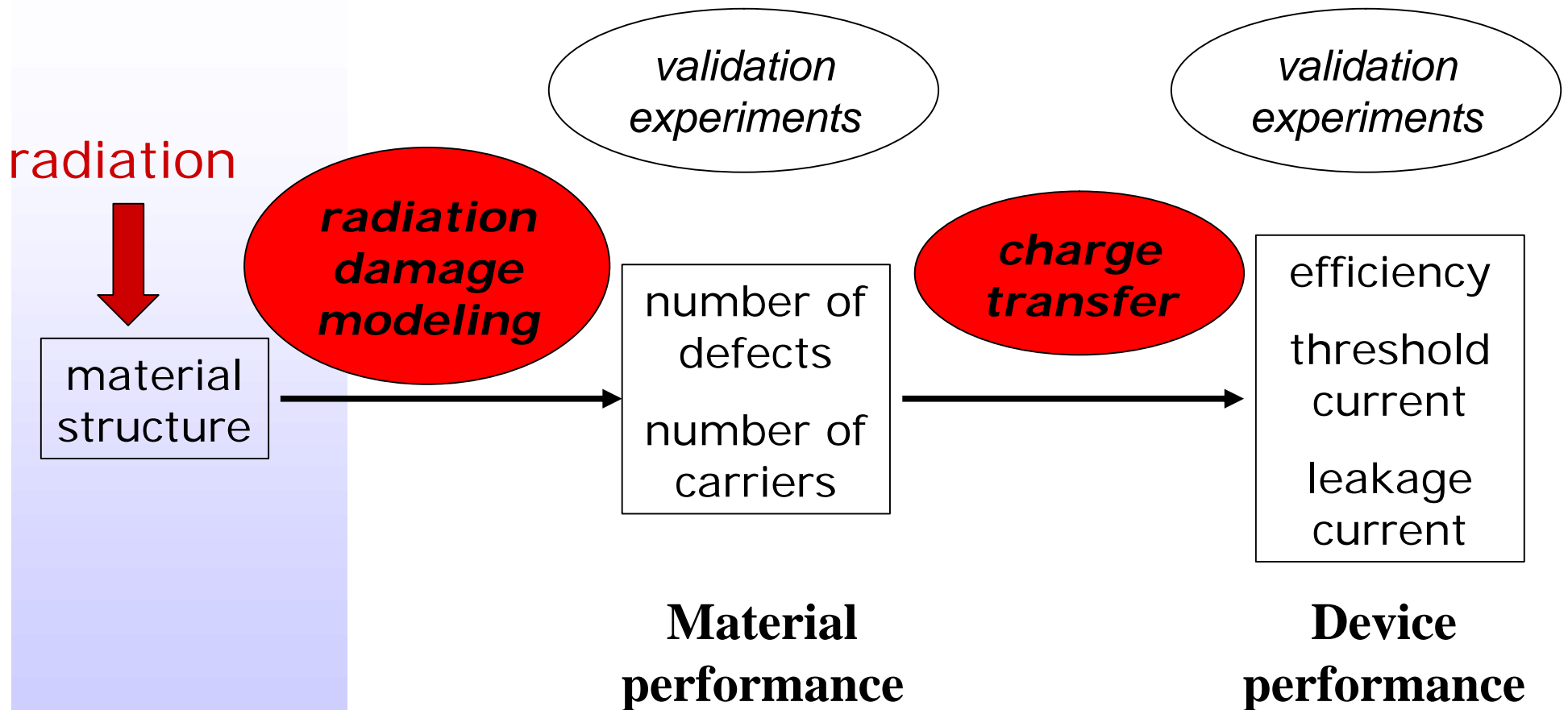
Laser Diodes and Photo Diodes under radiation

- Mainly studied for space applications
 - particle irradiation (electrons, protons, ions)
 - kGy level gamma doses
 - Observe the effects without in depth physical explanation
 - Damage correlation to the displacement (NIEL)
 - NIEL is a macro model for “bulk” structures
- ✓ *Modern O/E devices have complicated layered structures.*
- ✓ *We are interested in MGy level ionizing doses.*

Our final objectives are to

1. define predictive radiation damage models for 2 case studies
 1. P-i-n photodiodes – *Si, InGaAs...*
 2. Vertical-cavity surface-emitting lasers (VCSELs) - *GaAs, AlGaAs...*
2. find parts of the answer to
 1. Is degradation of modern optoelectronic devices due to bulk or interface damage ?
 2. How does downscaling of modern optoelectronics affect their radiation response ?
3. possibly optimize optoelectronic devices for use in nuclear environments

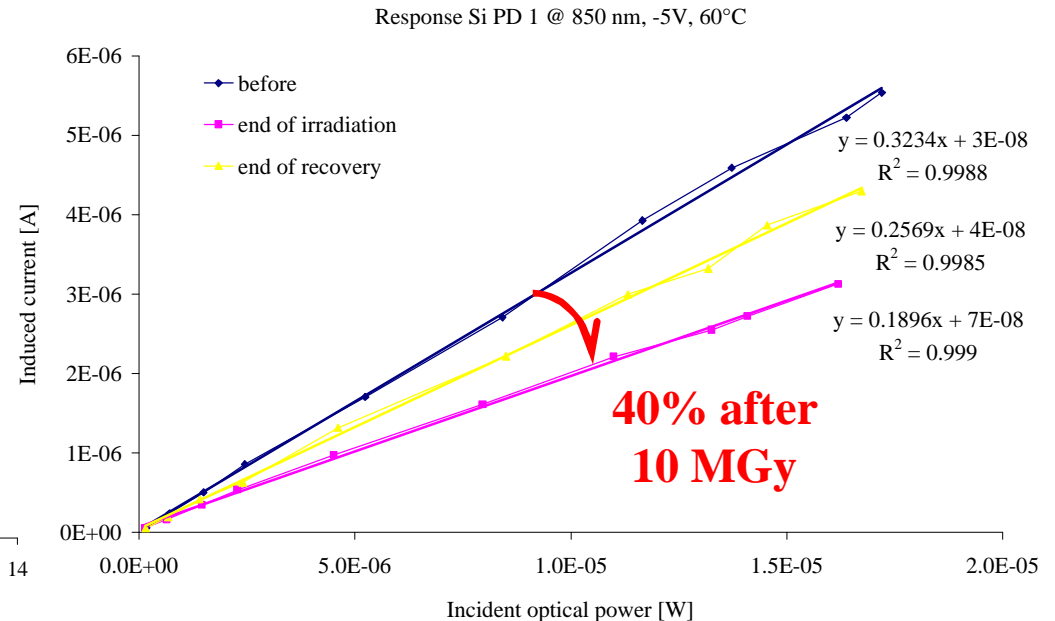
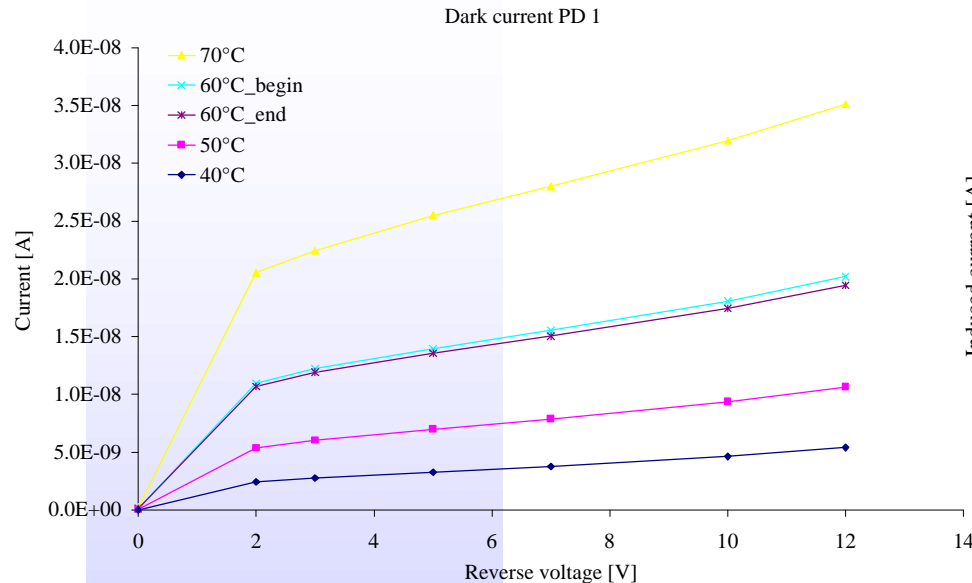
Our approach: from materials to devices



Si PD can withstand MGy dose levels, but...

➤ dark current increase

➤ responsivity decrease

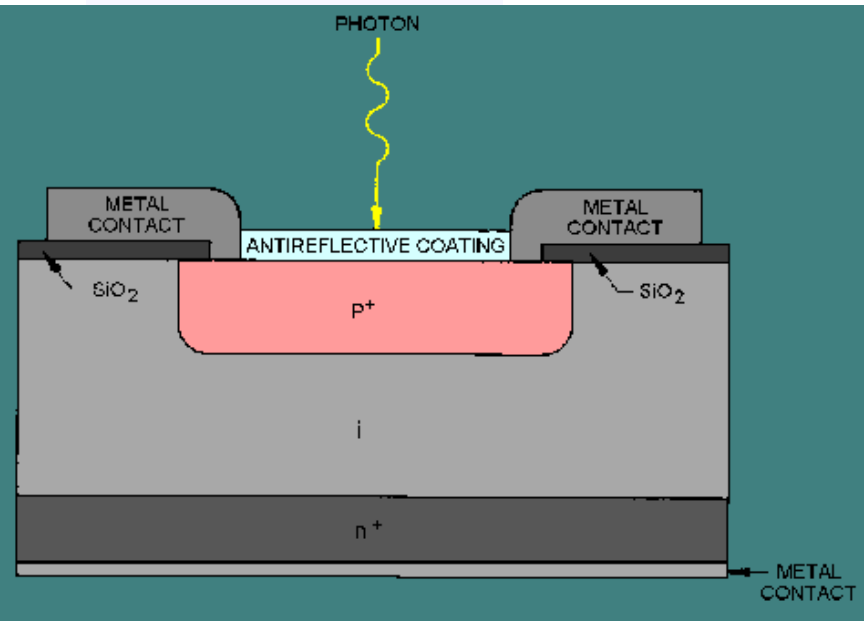


M. Van Uffelen et al., 2004, **SPIE Proceedings, vol. 5465**

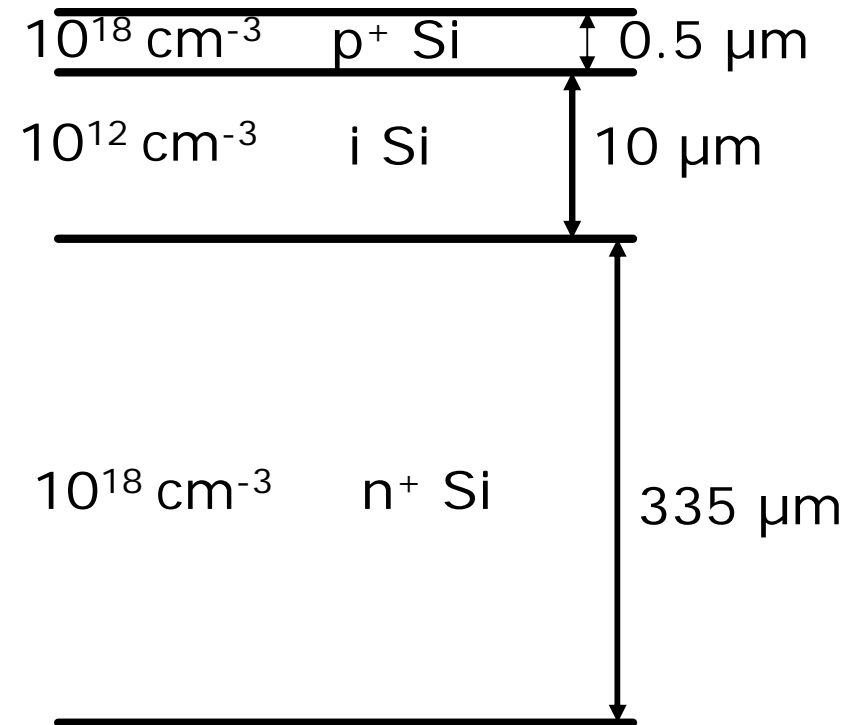
...this behavior is not yet well explained.

Test structures of a Si p-i-n photo diode

Device structure



Modeling structure



Onoda et al., NIM B 206 (2003) 444–447

Modeling tools for gamma radiation

Penelope

- Electron-photon transport
- 100 eV – 1 GeV

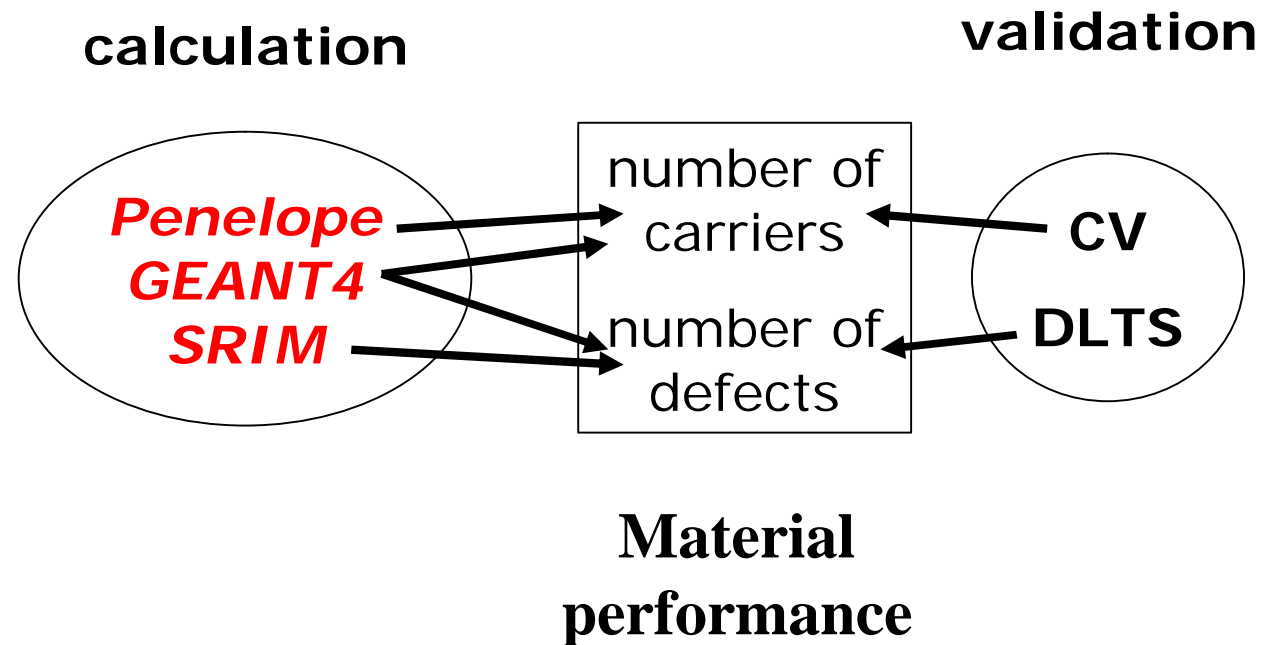
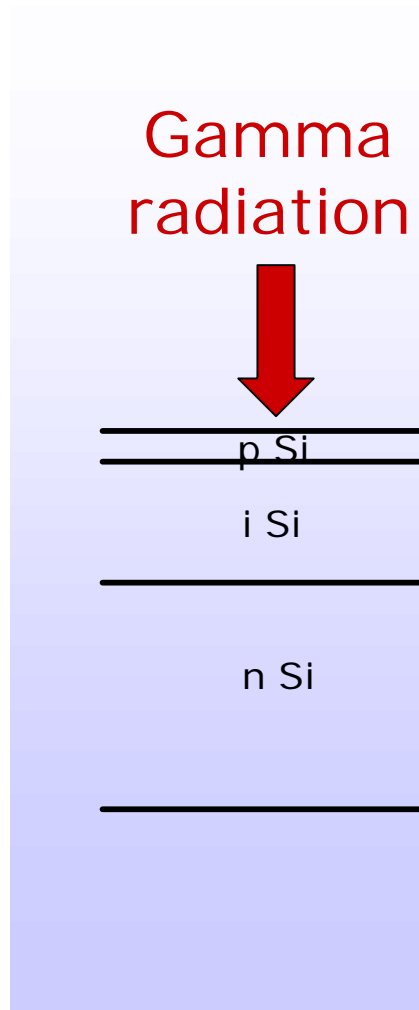
- ✓ Depth-distribution of deposited charge.
- ✓ Distribution of energy deposited into the target.

GEANT4

- CERN, Object-Oriented framework
- Electron, photon and particle transport
- Implemented the Penelope low energy physics

- ✓ Depth-distribution of deposited charge.
- ✓ Distribution of energy deposited into the target.
- ✓ Displacement profile

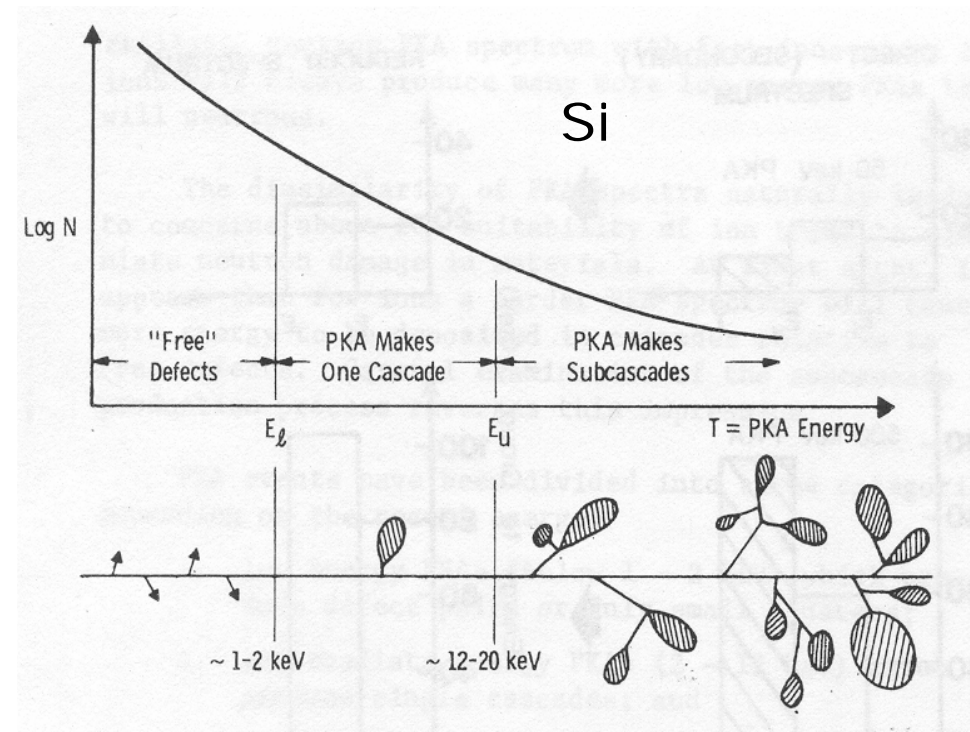
Detailed approach for material performance modeling



- Problem statement
 - Objectives
 - Approach
- **Progress**
 - **Physics of the processes**
 - **First calculations**
 - **CV measurements**
- Summary and Perspectives

Total ionization dose effects are playing significant role in case of Gamma radiation

- Displacement
 - Through Compton electrons
 - Primary Knock-on Atoms with energy lower than 1 keV
 - Only individual defects



S.Wood et al, *IEEE Trans. Nucl. Sci.*, 1981.

Displacement of target atoms in Si upon electron and gamma irradiation

K. Gill et al., *NIM A*, 1996

- vacancy introduction rate- 10^{-3}cm^{-1}
- divacancy introduction rate- 10^{-5}cm^{-1}
- type inversion after 110Mrad

L. Fedina et al., *Phys.stat.sol.(a)*, 1999.

- clusters of vacancies in Si formed after MeV electron irradiation
- depends on:
 - point defects
 - thickness of the sample
 - surface type
- clusters in Si are more stable compared to GaAs

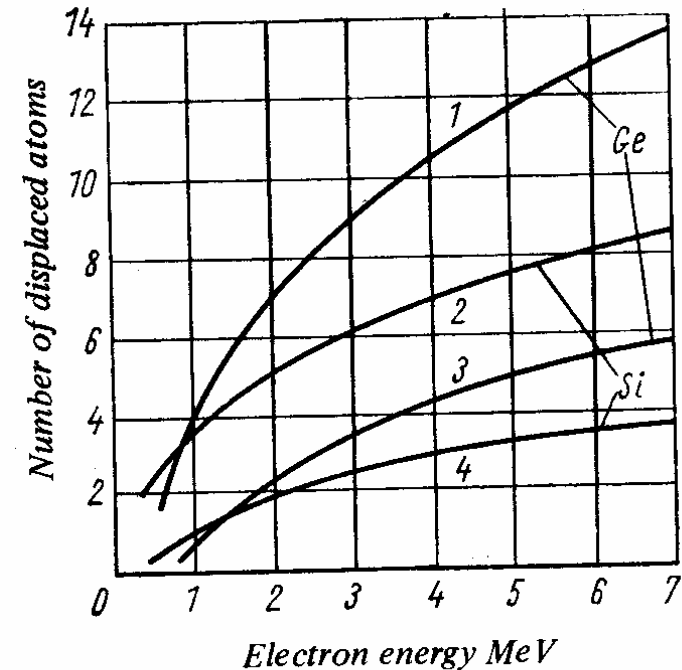
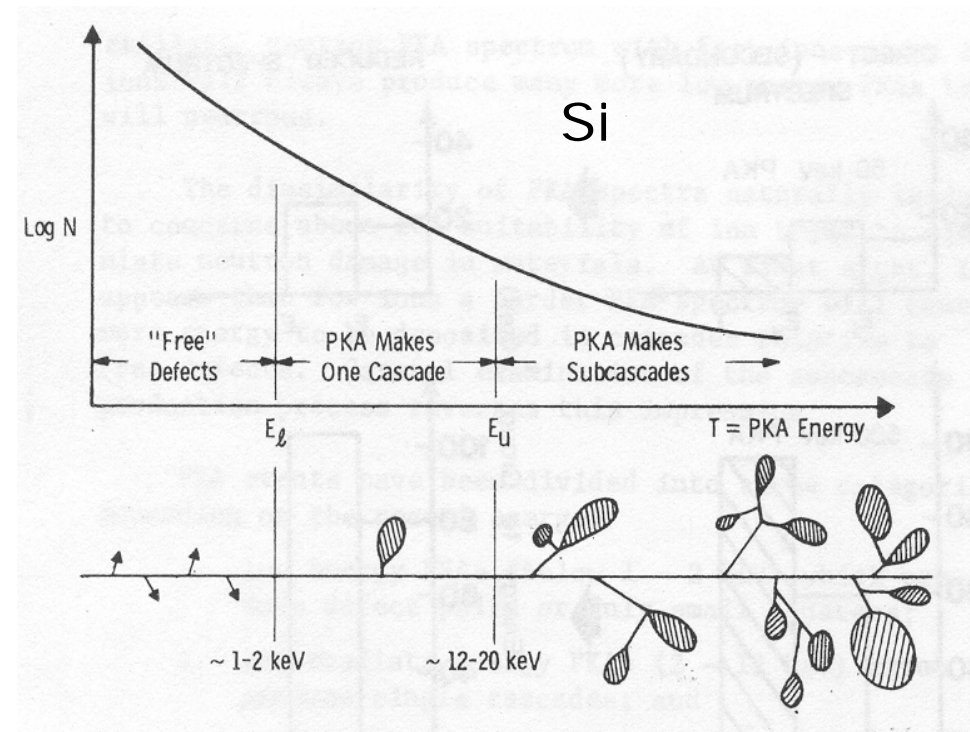


Figure 3. Number of displaced atoms of germanium and silicon per single incident fast electron [E_d 15 / 1,2/ and 30/3,4/ eV]

J. Kahn, *J.Appl.Phys.*, 1959.

Total ionization dose effects are playing significant role in case of Gamma radiation

- Displacement
 - Through Compton electrons
 - Primary Knock-on Atoms with energy lower than 1 keV
 - Only individual defects
- Heat
 - Annealing
- **Ionization**
 - Through Compton scattering and photo-electric effect



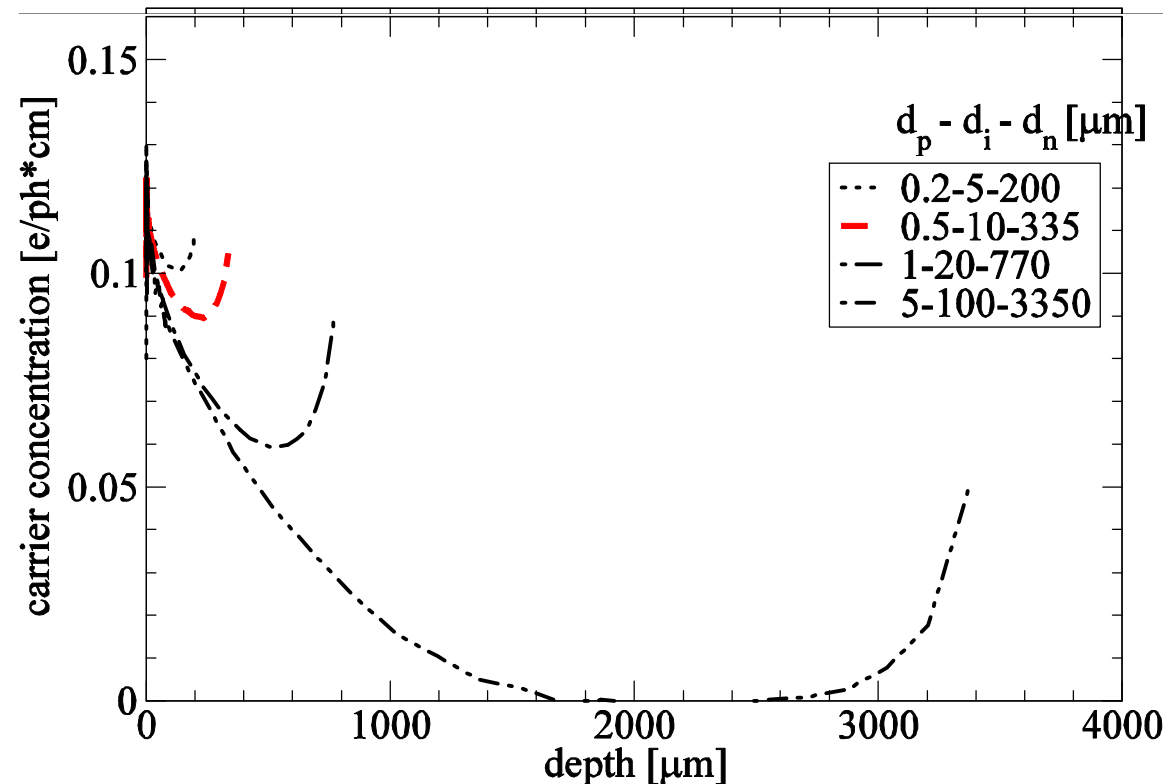
S.Wood et al, *IEEE Trans. Nucl. Sci.*, 1981.

Outcome from Penelope and its limitations

- Charge depth profiling-
consider only electron-
photon transport
 - thickness dependence
 - material dependence
- Limitations
 - does not take into account interface imperfections, bulk defects and impurities
 - does not include annealing
 - does not take dynamics into account (dose rate)
 - does not cover displacement
 - does not include electric field

Penelope calculations on Si p-i-n structures

- Two peaks structure
- There is not interface influence in the distribution
- The intensity of back peak decreases
- The code is not suitable for nm structures



Discussion

- insensitive to the doping levels
- missing any interface effects- the mean free path of the electrons is larger than the thickness of the device
- radiation induced carriers will affect lightly doped regions and those closer to the surface

Limits of the calculations

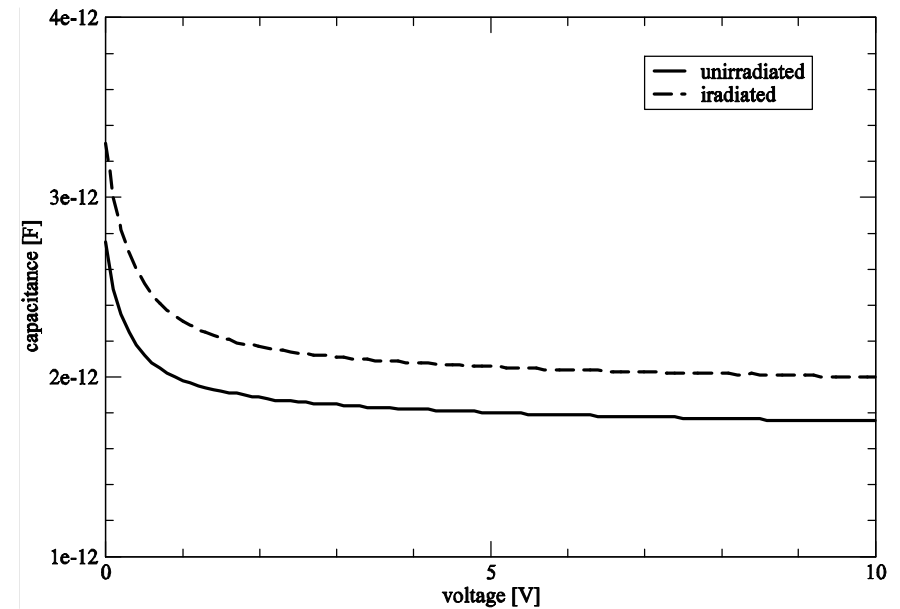
- temperature effects
- impurities and contaminations
- interface stresses
- dose rate effects and accumulation
phenomenology, MD

- electron particle transport
- electric field effects

GEANT4

First CV trials of Si p-i-n PD

- change in the material properties
- accumulation of charge in the oxide layer?
- intrinsic layer?
- package effects?



Summary

- Penelope calculates almost homogeneous distribution up to 500 μ m thickness of the structure
 - “bulk” effects are dominant
- the thinner the device the smaller the amount of radiation induced charges and the smaller the amount of displaced atoms
- lightly doped regions are more affected

Future work

- investigate electric field effects and displacement with Geant4
- additional CV measurements and interpretation
- looking for other suitable techniques to characterize devices